

Abstract of the Disclosure

**PLASMA PROCESSING APPARATUS AND METHODS FOR REMOVING
EXTRANEIOUS MATERIAL FROM SELECTED AREAS ON A SUBSTRATE**

Apparatus and methods for shielding a feature projecting from a first area on a substrate to a plasma while simultaneously removing extraneous material from a different area on the substrate with the plasma. The apparatus includes at least one
5 concavity positioned and dimensioned to receive the feature such that the feature is shielded from the plasma. The apparatus further includes a window through which the plasma removes the extraneous material. The method generally includes removing the extraneous material while shielding the feature against plasma exposure.

Fig. 1



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